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Signature: \_\_\_\_\_

*Richard A. Baumgartner*



**PATENT**

Attorney Docket No. NTI-019-2

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application

Inventor(s): Christophe Pierrat et al.

Application No.: 09/675,197

Filed: 09/29/2000

Title Dissection Of Edges With Projection Points In A  
Fabrication Layout For Correcting Proximity  
Effects

**PATENT APPLICATION**

Art Unit: 2812

Examiner: unknown

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**INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Listed below or on an attached Form PTO-1449 is information known to applicant(s). A copy of each listed publication and U.S. and foreign patent, except for pending U.S. applications, is being submitted herewith, along with a concise explanation of information in a foreign language, if any, pursuant to 37 C.F.R. §1.97-1.98.

Applicants respectfully request that the listed information be considered by the Examiner and be made of record in the above-identified application. If form PTO-1449 is enclosed, the Examiner is requested to initial and return it in accordance with MPEP § 609.

This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56.

- ☒ This statement qualifies under 37 C.F.R. § 1.97, subsection (b) because (check all that apply):
- ☐ (1) It is being filed within 3 months of the application filing date and is other than a continued prosecution application under § 1.53(d)  
-- OR --
  - ☐ (2) It is being filed within 3 months of entry of a national stage  
-- OR --
  - ☒ (3) It is being filed before the mail date of the first Office Action on the merits.  
-- OR --
  - ☐ (4) It is being filed before the mailing of a first Office Action after the filing of a request for continued examination under § 1.114
- ☐ 37 C.F.R. § 1.97(c). If this statement is being filed after the period specified in § 1.97(b), but before the mailing date of the earlier of a final office action under § 1.113, a notice of allowance under § 1.311, or an action that otherwise closes prosecution in the application, then:
- ☐ a certification as specified in § 1.97(e) is provided below; **or**
  - ☐ a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☐ 37 C.F.R. § 1.97(d). If this statement is being filed after the period specified in § 1.97(c), but on or before payment of the issue fee, then:
- A. a certification as specified in § 1.97(e) is completed below; **and**
  - B. a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☐ **Fee Authorization.** The Commissioner is hereby authorized to charge the above-referenced fees of \$ 180 and charge any additional fees or credit any overpayment associated with this communication to Deposit Account No. 50-0574 (Docket No. NTI-019-2).

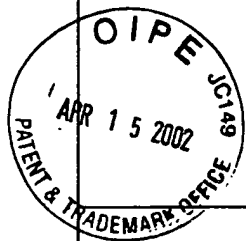
Respectfully submitted,

BEVER, HOFFMAN & HARMS, LLP

Dated: 4-11-02

By:   
Jeanette S. Harms, Reg. No. 35,537

Telephone: (408) 451-5900  
Customer No. 29477


**INFORMATION DISCLOSURE  
CITATION**
**PTO-1449**
**Atty. Docket No.**

NTI-019-2

**Serial No.**

09/675,197

**Applicant**

PIERRAT, Christophe

**Filing Date**

9/29/2000

**Group**

2812

**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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	4,895,780	1/23/1990	Nissan-Cohen, et al.	430	5	10/25/1988
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	6,249,597 B1	6/19/2001	Tsudaka	382	144	12/17/1998

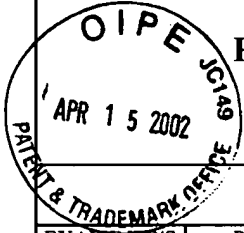
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 MPEP § 609; draw line through citation if not in conformance and not considered. Include  
 copy of this form with next communication to applicant.

<b>INFORMATION DISCLOSURE CITATION</b>  <b>PTO-1449</b>	<b>Atty. Docket No.</b>	<b>Serial No.</b>
	NTI-019-2	09/675,197
	<b>Applicant</b>	
	PIERRAT, Christophe	
	<b>Filing Date</b>	<b>Group</b>
	9/29/2000	2812

**FOREIGN PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
	2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/47981	9/23/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

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Serial No.

09/675,197

Applicant

PIERRAT, Christophe

Filing Date

9/29/2000

Group

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## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
	Choi, Y., et al., "Optical Proximity Correction on Attenuated Phase Shifting Photo Mask for Dense Contact Array", LG Semicon Company (11 pages).
	Lucas, K., et al., "Model Based OPC for 1st Generation 193nm Lithography", Motorola Inc., IDT assignee to IMEC (12 pages).
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	Dolainsky, C., et al., "Application of a Simple Resist Model to Fast Optical Proximity Correction", SPIE, Vol. 3051, pp. 774-780 (1997).
	Chen, J., et al., "Full-Chip Optical Proximity Correction with Depth of Focus Enhancement", Microlithography World, (5 pages) (1997).
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	Balasinski, A., et al., "Comparison of Mask Writing Tools and Mask Simulations for 0.16um Devices", IEEE, SEMI Advanced Semiconductor Manufacturing Conference, pp. 372-377 (1999).

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